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PATENT & TRADEMARK OFFICE

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Rathi, et al

Serial No.: 09/165,248

Confirmation No.: 7619

Filed: October 1, 1998

For: A Silicon Carbide Deposition for Use as a Barrier Layer and an Etch Stop

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§ Group Art Unit: 2823
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§ Examiner: G. R. Fourson, III
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CERTIFICATE UNDER 37 CFR 1.10

I hereby certify that this transmittal and the documents referred to as attached therein are being deposited on December 5, 2002 with the United States Postal Service in an envelope as "Express Mail Post Office to Addressee," mailing label No. EV 155456132 US US addressed to: Box CPA, Commissioner for Patents, Washington, D.C. 20231.

12/5/02 Date

Signature

Box CPA
Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

PRELIMINARY AMENDMENT

Prior to examining the case, Applicants request entry and consideration of the following remarks in response to a Final Office action dated September 5, 2002, having a shortened period of response set to expire on December 5, 2002. Although Applicant believes that no fee is due in conjunction with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/2966.X2/DSM/BCVD/JD, for any fees, including extension of time fees or excess claim fees, required to make this amendment timely and acceptable to the Office.

THE PENDING CLAIMS:

Sub G+H

15. A method for processing a substrate, comprising:

depositing a silicon carbide barrier layer on the substrate by a method comprising:

introducing an alkylsilane and a noble gas into a chamber;